

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IFW

In re patent application of

Lin HAI, et al.



Serial No.: 10/573,446

Group Art Unit: 2871

Filed: March 24, 2006

Examiner: Unknown

For: PLASMA DISPLAY PANEL AND METHOD OF  
MANUFACTURING SAME

Honorable Commissioner of Patents  
Alexandria, Virginia 22313-1450

**INFORMATION DISCLOSURE STATEMENT**

Sir:

Under the provisions of 37 CFR §1.97 through §1.98 and pursuant to Applicants' duty of disclosure under 37 CFR §1.56, Applicants respectfully bring the following documents cited in the International Search Report (previously filed on July 13, 2006) in a counterpart foreign application and listed on the attached form PTO-1449, to the attention of the Examiner in charge of the above-identified application. Further, Japanese No. JP2002-033053 corresponds to US Patent No. 6,788,373. Also, JP2003-031130 corresponds to US Patent No. 6,674,238, and JP Hei 10-233157 corresponds to US Patent Nos. 6,013,309 and 6,379,783.

This citation does not constitute an admission that the references are relevant or material to the claims. They are only cited as constituting related art of which Applicants are aware.

In compliance with the concise explanation requirement under 37 CFR §1.98(a)(3) for foreign language documents, Applicants enclose herewith a copy of the International Search Report citing such documents, together with an English-language version (if not already included) of that portion of the Search Report indicating the degree of relevance found by the foreign office. Further, English language abstracts are attached to the references.

Please charge any deficiencies in fees and credit any overpayment of fees to Attorney's Deposit Account No. 50-0481.

Respectfully submitted,

Sean M. McGinn, Esq.  
Registration No. 34,386

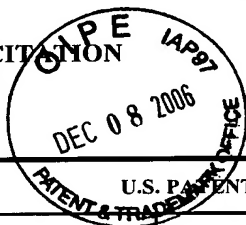
Date: 12/8/06

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(703) 761-4100  
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# INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)



|  |   |
|--|---|
| Docket Number (Optional)<br><b>04-41 PUS</b> | Application Number<br><b>10/573,446</b> |
| Applicant(s)<br><b>Lin HAI, et al.</b>       |   |
| Filing Date<br><b>March 24, 2006</b>         | Group Art Unit<br><b>2871</b>           |

## U.S. PATENT DOCUMENTS

| *EXAMINER<br>INITIAL | REF | DOCUMENT NUMBER | DATE       | NAME          | CLASS | SUBCLASS | FILING DATE<br>IF APPROPRIATE |
|----------------------|-----|-----------------|------------|---------------|-------|----------|-------------------------------|
|                      |     | 6,013,309       | 01/11/2000 | Kim, et al.   |       |          |                               |
|                      |     | US 6,788,373 B2 | 09/07/2004 | Ito, et al.   |       |          |                               |
|                      |     | US 6,674,238 B2 | 01/06/2004 | Otani, et al. |       |          |                               |
|                      |     | US 6,379,783 B1 | 04/30/2002 | Kim, et al.   |       |          |                               |
|                      |     |                 |            |               |       |          |                               |

## U.S. PATENT APPLICATION PUBLICATIONS

| *EXAMINER<br>INITIAL | REF | DOCUMENT NUMBER | DATE | NAME | CLASS | SUBCLASS | FILING DATE<br>IF APPROPRIATE |
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## FOREIGN PATENT DOCUMENTS

|  | REF | DOCUMENT NUMBER | DATE       | COUNTRY | CLASS | SUBCLASS | Translation |    |
|--|-----|-----------------|------------|---------|-------|----------|-------------|----|
|  |     |                 |            |         |       |          | YES         | NO |
|  |     | 2003-31130      | 01/03/2003 | Japan   |       |          | ABS         |    |
|  |     | 2002-33053      | 01/31/2002 | Japan   |       |          | ABS         |    |
|  |     | 10/233157       | 09/02/1998 | Japan   |       |          | ABS         |    |
|  |     | 7-37510         | 02/07/1995 | Japan   |       |          | ABS         |    |
|  |     | 2000-156153     | 06/06/2000 | Japan   |       |          | ABS         |    |

## OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

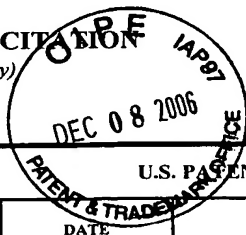
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|  |  | International Search Report dated January 18, 2005 |
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EXAMINER

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**INFORMATION DISCLOSURE CITATION**  
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|--|---|
| Docket Number (Optional)<br><b>04-41 PUS2001</b> | Application Number<br><b>10/573,446</b> |
| Applicant(s)<br><b>Lin HAI, et al.</b>           |   |
| Filing Date<br><b>March 24, 2006</b>             | Group Art Unit<br><b>28717</b>          |

**U.S. PATENT DOCUMENTS**

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|  | REF | DOCUMENT NUMBER | DATE       | COUNTRY | CLASS | SUBCLASS | Translation |    |
|--|-----|-----------------|------------|---------|-------|----------|-------------|----|
|  |     |                 |            |         |       |          | YES         | NO |
|  |     | 7-296718        | 11/10/1995 | Japan   |       |          | ABS         |    |
|  |     | 9-167566        | 06/24/1997 | Japan   |       |          | ABS         |    |
|  |     | 8-287823        | 11/01/1996 | Japan   |       |          | ABS         |    |
|  |     | 7-192630        | 07/28/1995 | Japan   |       |          | ABS         |    |
|  |     | 2001-76629      | 03/23/2001 | Japan   |       |          | ABS         |    |

**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)

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